
IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of: Alton Hugh Phillips

Attorney Docket No.: NIKOP063/PA0
646

Application No.: NEW

Examiner: UNASSIGNED

Filed: HEREWITH

Group: UNASSIGNED

Title: POSITION CONTROL AND HEAT
DISSIPATION FOR
PHOTOLITHOGRAPHY SYSTEMS

**INFORMATION DISCLOSURE STATEMENT
37 CFR §§1.56 AND 1.97(b)**

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450


Dear Sir:

The references listed in the attached PTO Form 1449, copies of which are attached, may be material to examination of the above-identified patent application. Applicants submit these references in compliance with their duty of disclosure pursuant to 37 CFR §§1.56 and 1.97. The Examiner is requested to make these references of official record in this application.

This Information Disclosure Statement is not to be construed as a representation that a search has been made, that additional information material to the examination of this application does not exist, or that these references indeed constitute prior art.

This Information Disclosure Statement is: (i) filed within three (3) months of the filing date of the above-referenced application, (ii) believed to be filed before the mailing date of a first Office Action on the merits, or (iii) believed to be filed before the mailing of a first Office Action after the filing of a Request for Continued Examination under §1.114. Accordingly, it is believed that no fees are due in connection with the filing of this Information Disclosure Statement. However, if it is determined that any fees are due, the Commissioner is hereby authorized to charge such fees to Deposit Account 500388 (Order No. NIKOP063).

Respectfully submitted,
BEYER WEAVER & THOMAS, LLP


Phillip P. Lee
Registration No. 46,866

P.O. Box 778
Berkeley, CA 94704-0778

Form 1449 (Modified) Information Disclosure Statement By Applicant (Use Several Sheets if Necessary)	Atty Docket No. NIKOP063/PA0 646	Application No.: NEW
	Applicant: Alton Hugh Phillips Filing Date HEREWITH	Group UNASSIGNED

U.S. Patent or Publication Documents

Examiner Initial	No.	Patent No.	Date	Patentee	Class	Sub-class	Filing Date
	A1	6,570,645	5/27/03	Korenaga et al.			
	A2	6,037,680	3/14/00	Korenaga et al.			
	A3	5,841,250	11/24/98	Korenaga et al.			
	A4	6,177,987	1/23/01	Korenaga			
	A5	6,107,703	8/22/00	Korenaga			
	A6	6,678,038	1/13/04	Binnard			
	A7	6,618,120	9/9/03	Ueta			
	A8	6,597,435	7/22/03	Poon et al.			
	A9	6,555,936	4/29/03	Tanaka et al.			
	A10	6,538,719	4/25/03	Takahashi, et al.			
	A11	6,504,162	1/27/03	Binnard et al.			
	A12	6,496,248	12/17/03	Tanaka			
	A13	6,490,105	12/3/02	Hagy			
	A14	6,597,433	7/22/03	Renkens, et al.			
	A15	6,342,942	6/29/99	Uzawa			
	A16	2003/0223125	12/4/03	Sewell, Harry; et al.			
	A17	2002/0159046	10/31/02	Binnard et al.			
	A18	2002/0109823	8/15/02	Binnard et al.			
	A19	200/0041377	4/11/02	Hagiwara et al.			

Foreign Patent or Published Foreign Patent Application

Examiner Initial	No.	Document No.	Publication Date	Country or Patent Office	Class	Sub-class	Translation	
							Yes	No
	B1	EP1367444	3/12/03	EPO			X	
	B2	EP1376052	2/1/04	EPO			X	
	B3	EP1137054	9/26/01	EPO			X	
	B4	WO01/81171	11/1/01	WIPO			X	
	B5	JP2002313716 Accompanied by English- language abstract	10/25/02	JPO				X

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	Applicant: Alton Hugh Phillips Filing Date HEREWITH	Group UNASSIGNED

Other Documents

Examiner Initial	No.	Author, Title, Date, Place (e.g. Journal) of Publication
	C1	Meiling et al., "Progress of the EUVL Alpha Tool," Proceedings of SPIE, Vol. 4343, pp. 38-50, 2001
	C2	Gui et al., "Extended Front-to-Back Alignment Capability for MEMS/MOEMS Applications," Proceedings of SPIE, Vol. 4688, pp. 867-873, 2002
	C3	Sluijk et al., "Performance Results of a New Generation of 300 mm Lithography Systems," Proceedings of SPIE, Vol. 4346, pp. 544-557, 2001
	C4	Klassen et al., "Dynamice Performance of DUV Step & Scan Systems and Process Latitude," Proceedings of SPIE, Vol. 4000, pp. 776-784, 2000
	C5	Meiling et al., "The EUV Program at ASML: An Update," Proceedings of SPIE, Vol. 5037, pp. 24-35, 2003
Examiner		Date Considered

Examiner: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.